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10/529742

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

HIROSHI SHIHO, ET AL.

: ATTN: APPLICATION DIVISION

SERIAL NO: 10/529,742

DEIGHE 110. 10/323,7 12

FILED: MARCH 29, 2005

FOR:

POLISHING PAD FOR

SEMICONDUCTOR WAFER AND

LAMINATED BODY FOR

POLISHING OF SEMICONDUCTOR WAFER EQUIPPED WITH THE SAME AS WELL AS METHOD FOR POLISHING OF SEMICONDUCTOR

WAFER

PRELIMINARY AMENDMENT

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Prior to a first examination on the merits, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.